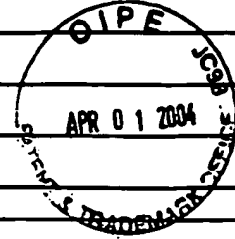


INFORMATION DISCLOSURE CITATION



Atty. Docket No.	04329.2802-01000	Appln. No.	10/698,456
Applicant	Mari INOUE		
Filing Date	November 3, 2003	Group:	To be Assigned



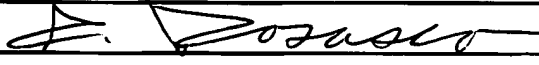
U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate

FOREIGN PATENT DOCUMENTS

	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
	Japanese Patent Application KOKAI Publication No. 2000-20564	01/21/2000	Japan			NO
	Korean Patent Application Publication No. 2000-23031	04/25/2000	Korea			NO

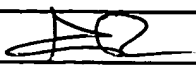


OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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Atty. Docket No.	04329.2802-01	Appln. No.	n/a
Applicant	Mari INOUE		
Filing Date	November 3, 2003	Group:	n/a

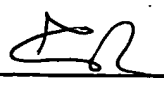

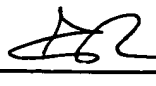
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	4,499,595	02-1985	Masaitis et al.			


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	2000-75467	3/14/00	Japan			Abstract
	2000-20564	01/21/00	Japan			Abstract
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	Int'l Sematech "Advanced Process Control Framework Initiative Project Overview" June 30, 1999 Technology Transfer No. 99053735A-TR http://www.sematech.org/public/docubase/document/3735atr.pdf visited 4/4/2003
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Atty. Docket No.	04329.2802-01	Appln. No.	n/a
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